

Overview on Low Gain Avalanche Detectors

J. Lange

for many people working on this

Terascale Detector Workshop München, 28 February 2018

LGAD in a Nutshell

- Developed by CNM Barcelona and CERN RD50 collaboration

- Now also Hamamatsu, FBK, BNL, Micron
- Inspired by charge multiplication in irradiated Si detectors
J. Lange et al., NIM A622(2010)49

- Could be considered as large APD/SiPM with lowered gain + segmentation for charged particle tracking/X-rays

- But historical development/philosophy is other way round:
Standard segm. n-p silicon detector + built-in p multiplication layer

→ High E field

→ Moderate gain ~10-20

→ Increases signal

→ Keeps noise limited

Increased S/N

- Multiplication allows thinner detectors (now 35-50 μm)

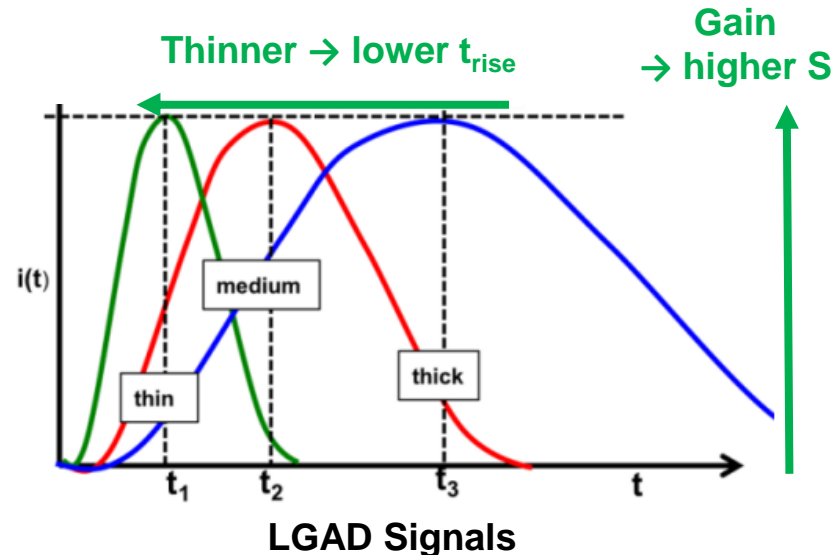
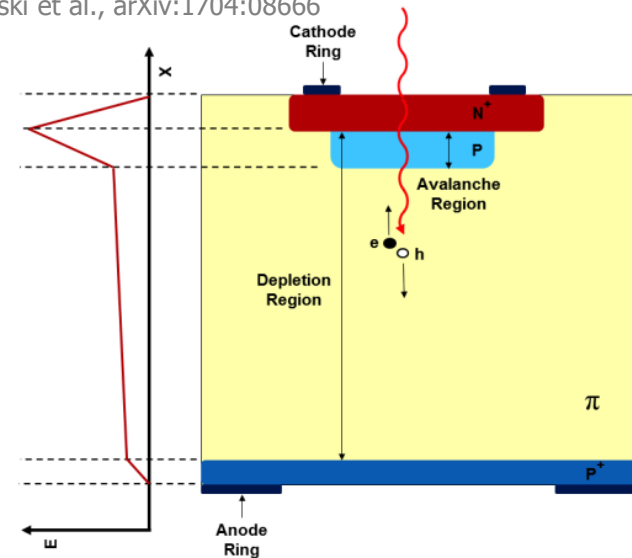
→ Fast charge collection (~1 ns)

→ Small rise time (~400 ps)

→ Excellent time resolution < 30 ps

$$\sigma_{\text{Jitter}} = \frac{N}{(dV/dt)} \simeq \frac{t_{\text{rise}}}{(S/N)}$$

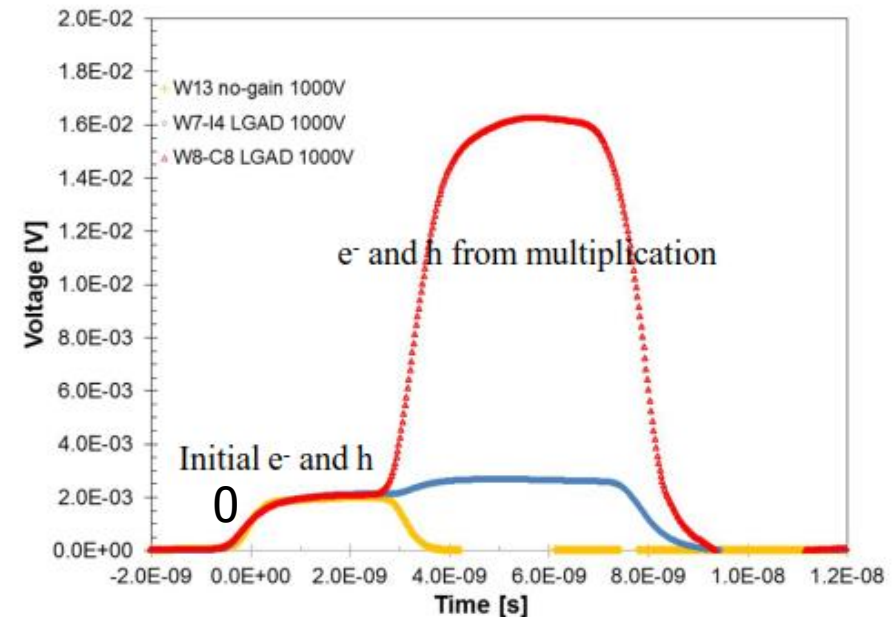
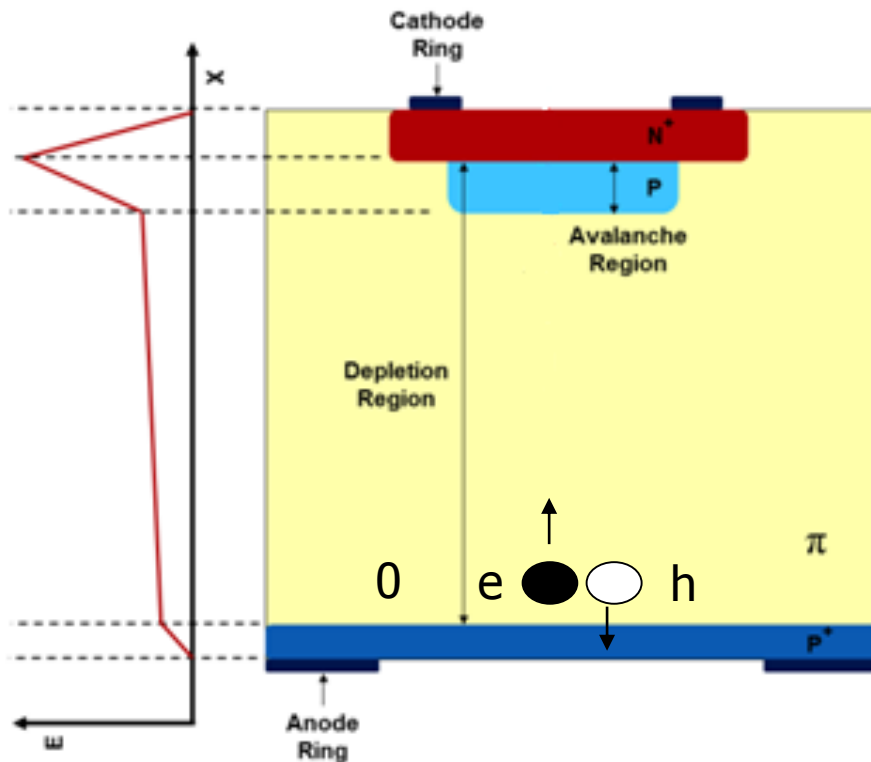
G. Pellegrini et al., NIM A765 (2014) 12
H. Sadrozinski et al., arXiv:1704.08666



Signal Formation – Back Side Injection

- Measurable signal induced by Ramo theorem
 - Back side charge injection (alpha or red laser) -> Follow charge carrier as probe of E field and multiplication
- 0) e-h pairs created at back side, h immediately collected

$$I_{e,h}(t) = \frac{eN_{e,h}(t)}{d} v_{dr,e,h}(t)$$

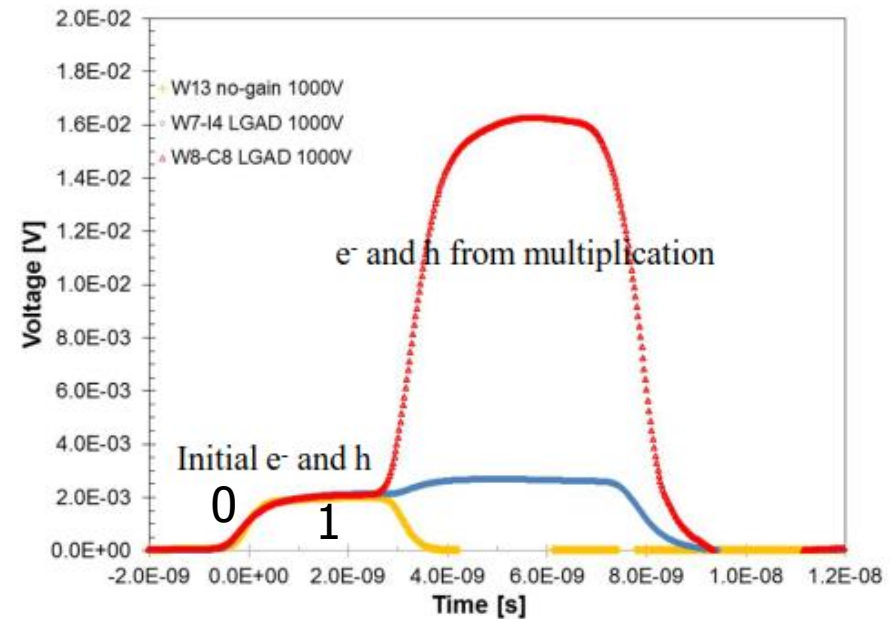
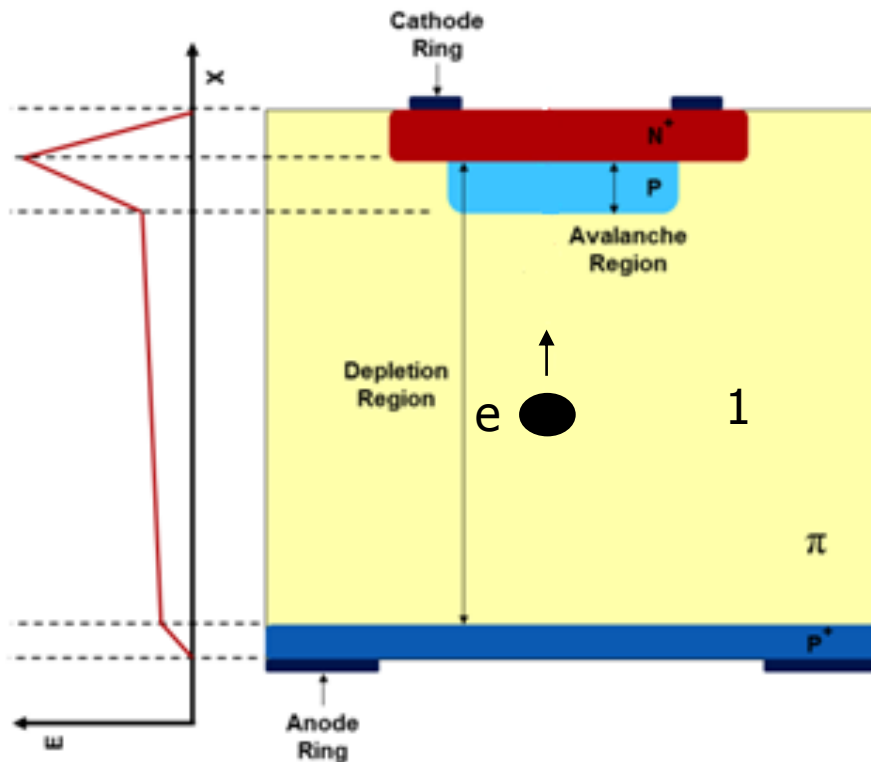


Hartmut Sadrozinski
23rd RD50 workshop

Signal Formation – Back Side Injection

- Measurable signal induced by Ramo theorem
- Back side charge injection (alpha or red laser) -> Follow charge carrier as probe of E field and multiplication
 - e-h pairs created at back side, h immediately collected
 - e drift towards high field from back to front

$$I_{e,h}(t) = \frac{eN_{e,h}(t)}{d} v_{dr,e,h}(t)$$

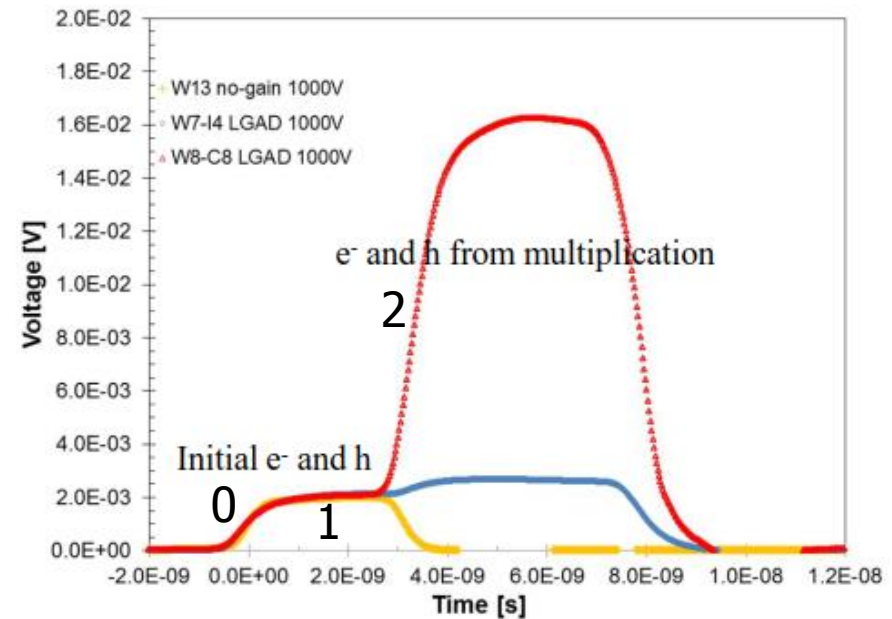
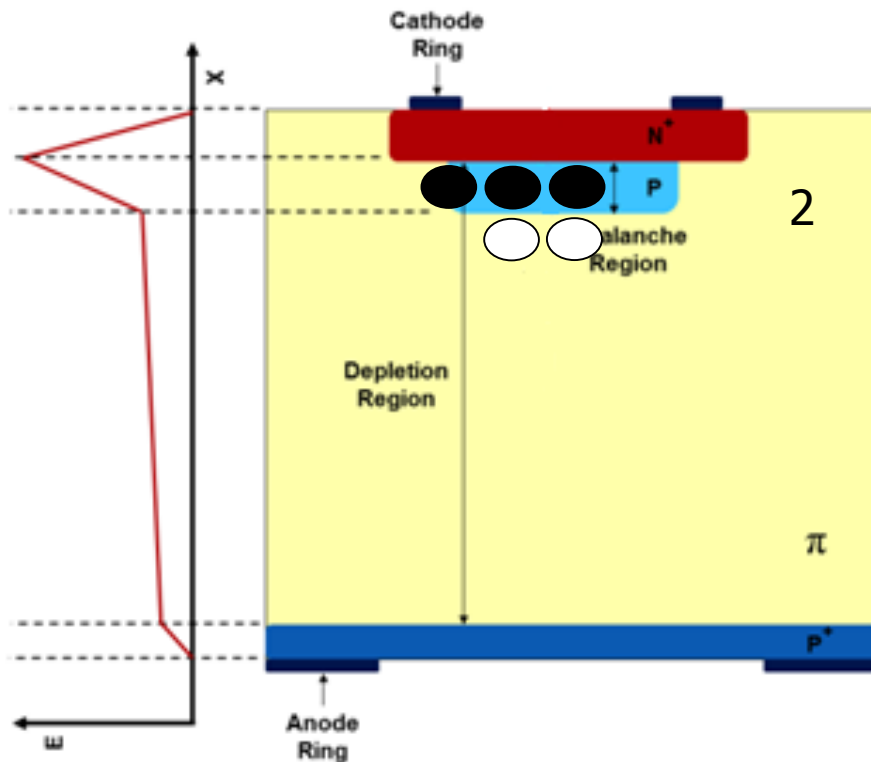


Hartmut Sadrozinski
23rd RD50 workshop

Signal Formation – Back Side Injection

- Measurable signal induced by Ramo theorem
- Back side charge injection (alpha or red laser) -> Follow charge carrier as probe of E field and multiplication
 - e-h pairs created at back side, h immediately collected
 - e drift towards high field from back to front
 - e multiply in high field multiplication region

$$I_{e,h}(t) = \frac{eN_{e,h}(t)}{d} v_{dr,e,h}(t)$$

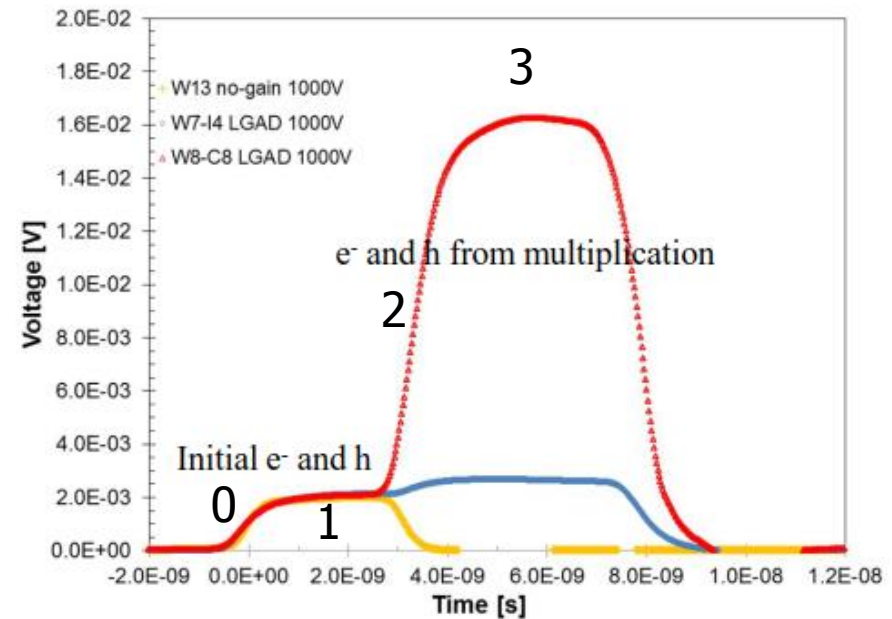
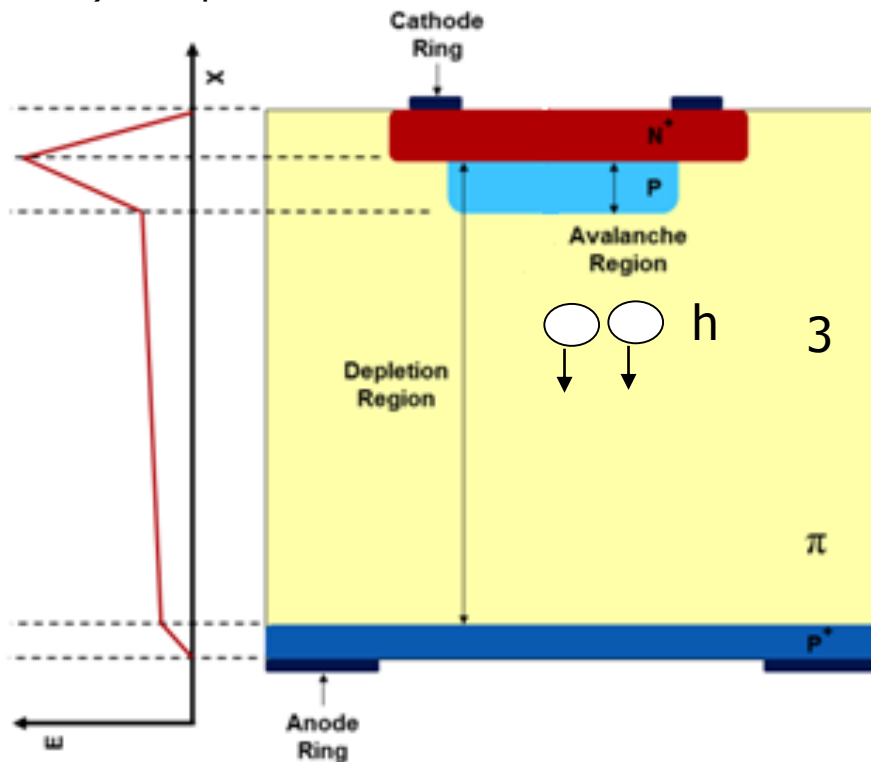


Hartmut Sadrozinski
23rd RD50 workshop

Signal Formation – Back Side Injection

- Measurable signal induced by Ramo theorem
- Back side charge injection (alpha or red laser) -> Follow charge carrier as probe of E field and multiplication
 - e-h pairs created at back side, h immediately collected
 - e drift towards high field from back to front
 - e multiply in high field multiplication region
 - multiplication h drift towards the back

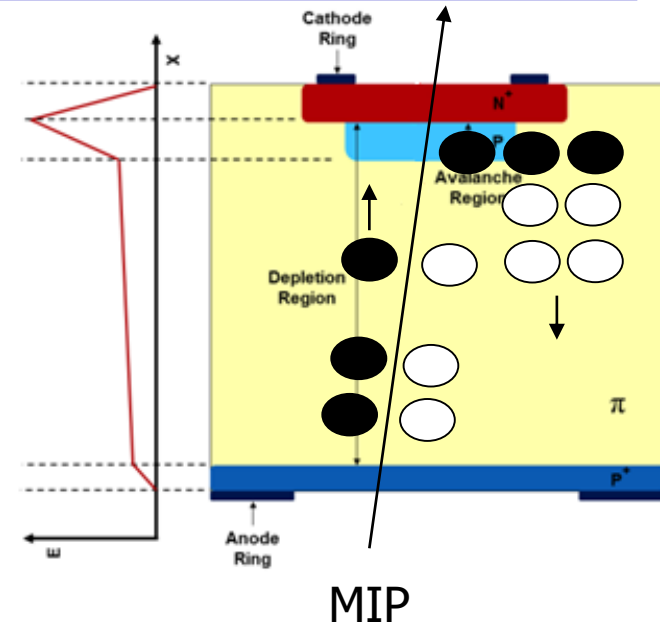
$$I_{e,h}(t) = \frac{eN_{e,h}(t)}{d} v_{dr,e,h}(t)$$



Hartmut Sadrozinski
23rd RD50 workshop

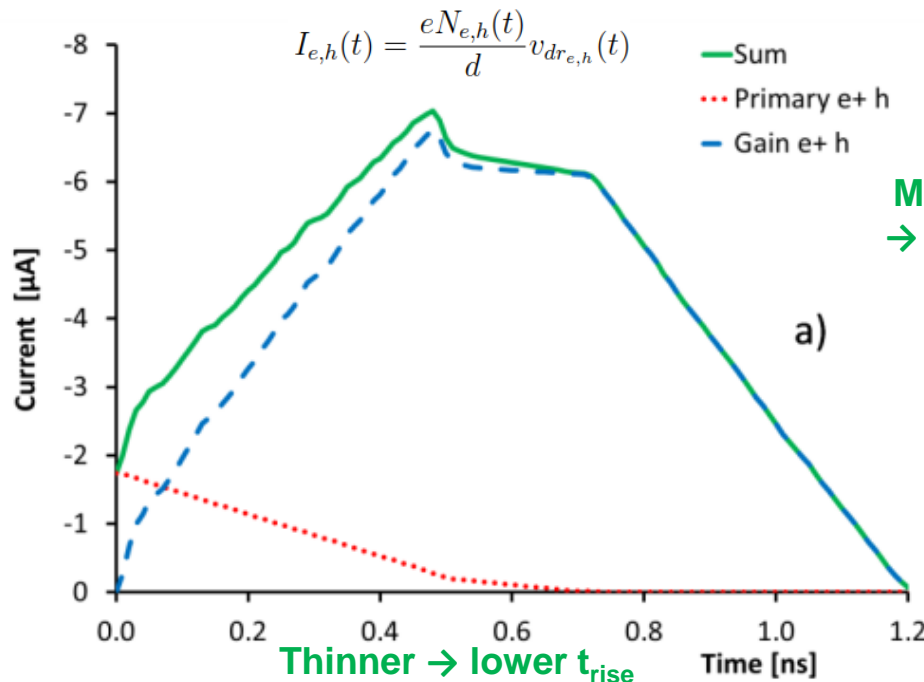
Signal Formation – MIP

- MIP is ionizing along its path
 - Rather uniformly in depth
 - But Landau fluctuations present
- Signal formation is sum of individual charge packages
 - Primary e+h
 - Constant multiplication until all e have reached front side ("gain e+h")
 - Then only h signal



Weightfield2 Simulation

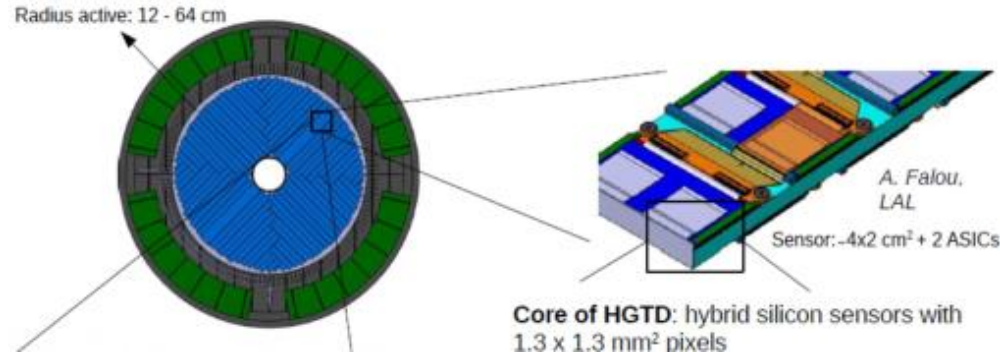
F. Cenna et al., NIM A 796



LGAD Applications

- HEP timing detectors
(ATLAS HGTD, CMS ETL, AFP, CT-PPS)

- Pile-up rejection:
assign each particle a vertex via collision time
- 30 ps time resolution
- Pads $\sim 1 \text{ mm}^2$

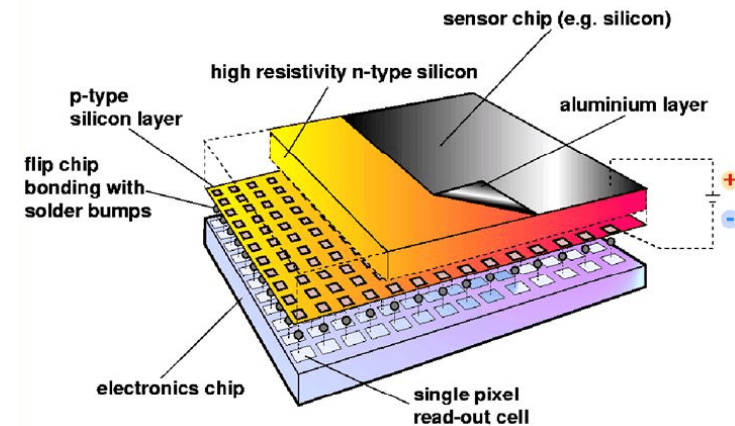


- "4D tracking" (future)

- $\sim 50 \text{ } \mu\text{m}$ pixel + $\sim 30 \text{ ps}$ timing
- "All in one"

- Photon science: soft X-ray

- Soft X-rays $\sim 1 \text{ keV}$
- Gain boosts small signal above ASIC thresholds
→ standard ASICs (AGIPD, Medipix, ...) + infrastructure can be used



- Medical: Radiotherapy

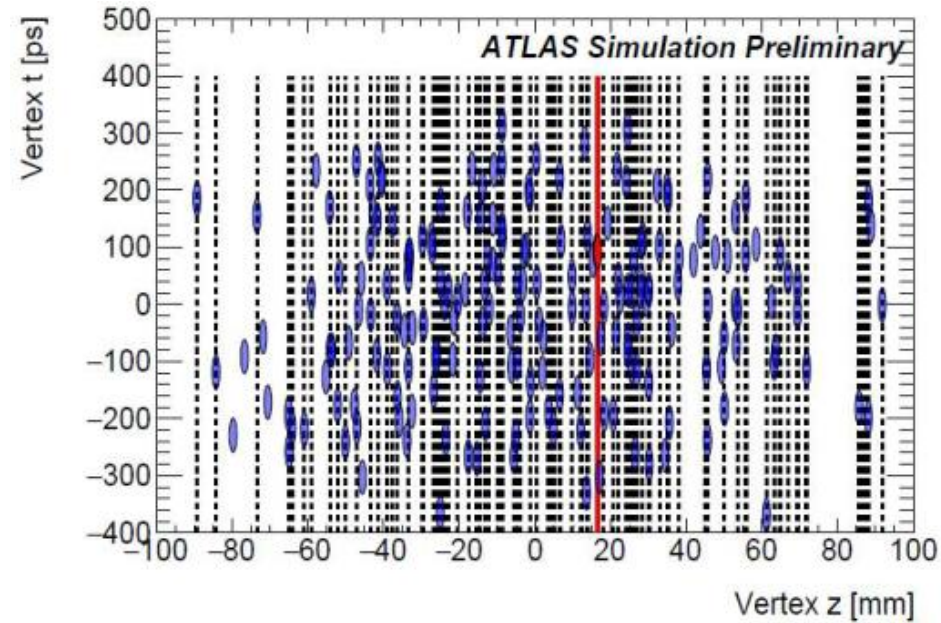
- Measure high rate beams + ToF for precise energy ($\sim 10\text{-}100 \text{ MeV p}$)

- ...?

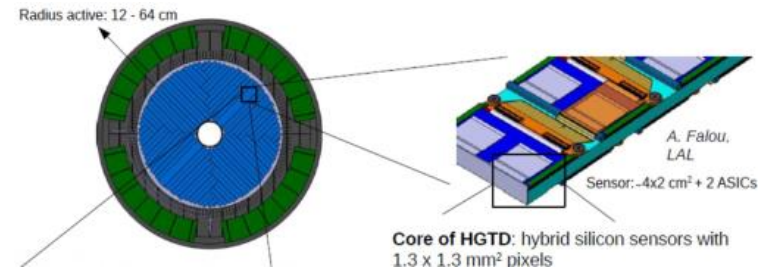
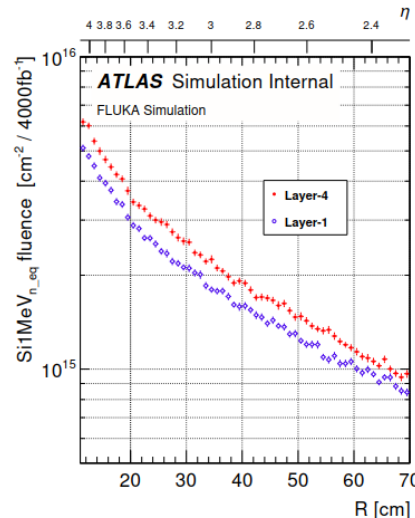
HL-LHC Timing Layers

- The quest: assign each particle a vertex
 - Tracker resolution in some regions not precise enough (e.g. at high eta)
 - Collision time is independent vertex information
 - further pile-up suppression
 - helps to keep performance (b-tagging, jet pile-up, lepton isolation,...)
- New planned timing detectors for ATLAS and CMS
 - ~30 ps time resolution/track, $1\text{--}5 \times 10^{15} n_{\text{eq}}/\text{cm}^2$ rad.-hard
 - LGAD pads $\sim 1 \text{ mm}^2$, $\sim 10 \text{ m}^2$ of Si each

See talk by L. Masetti



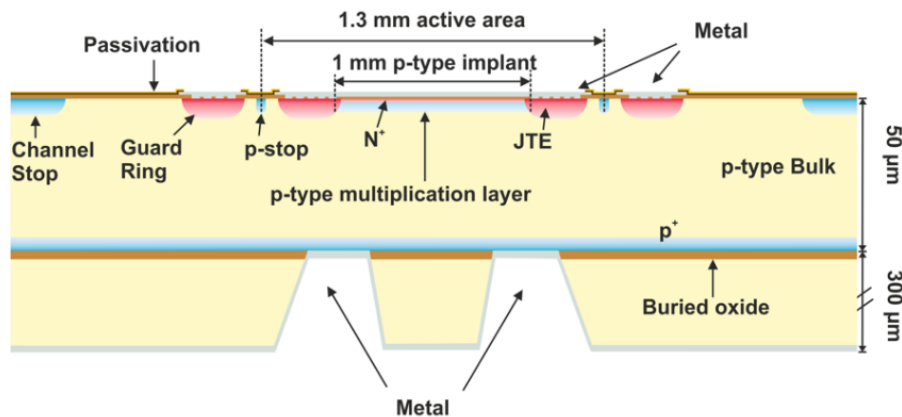
	ATLAS	CMS
Name	HGTD	ETL
Eta	2.4-4.0	1.6-3.0 (+barrel)
Layers	2-3	1
Resol. [ps]	30	30-35
Pad [mm ²]	1.3x1.3	1.0x3.0
Max. Fluence [$n_{\text{eq}}/\text{cm}^2$]	5 (1 repl.)	1



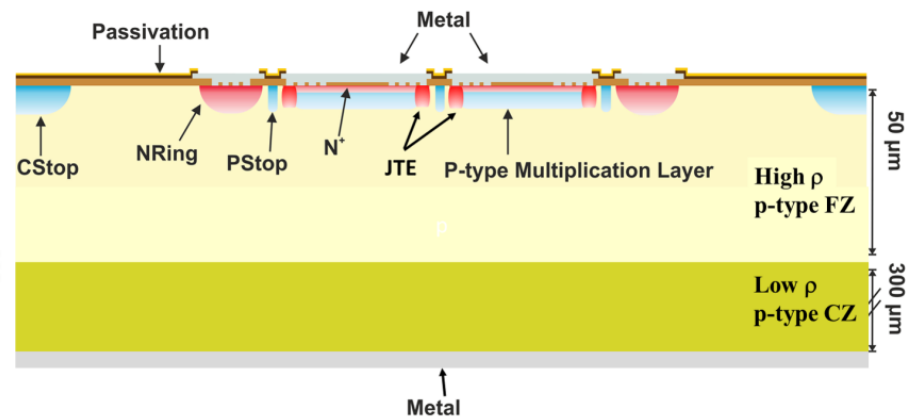
LGAD Technology

- Produced by CNM, FBK, HPK, BNL, Micron
- Pioneered on 300 μm thickness and 4"
- Now 6" and different technologies for 35-50 μm active thickness/substrate (Epi, SOI, Si-Si)
- Usually B used for highly doped p-type multiplication layer
 - Also Ga and additional C-spray under investigation for improved radiation hardness (see later)
- Junction terminations (e.g. JTE) needed to avoid local high fields and early breakdown at implantation edges
 - Drawback: no-gain inter-pad gap

CNM SOI, single pad



CNM Si-Si, 2x2 array



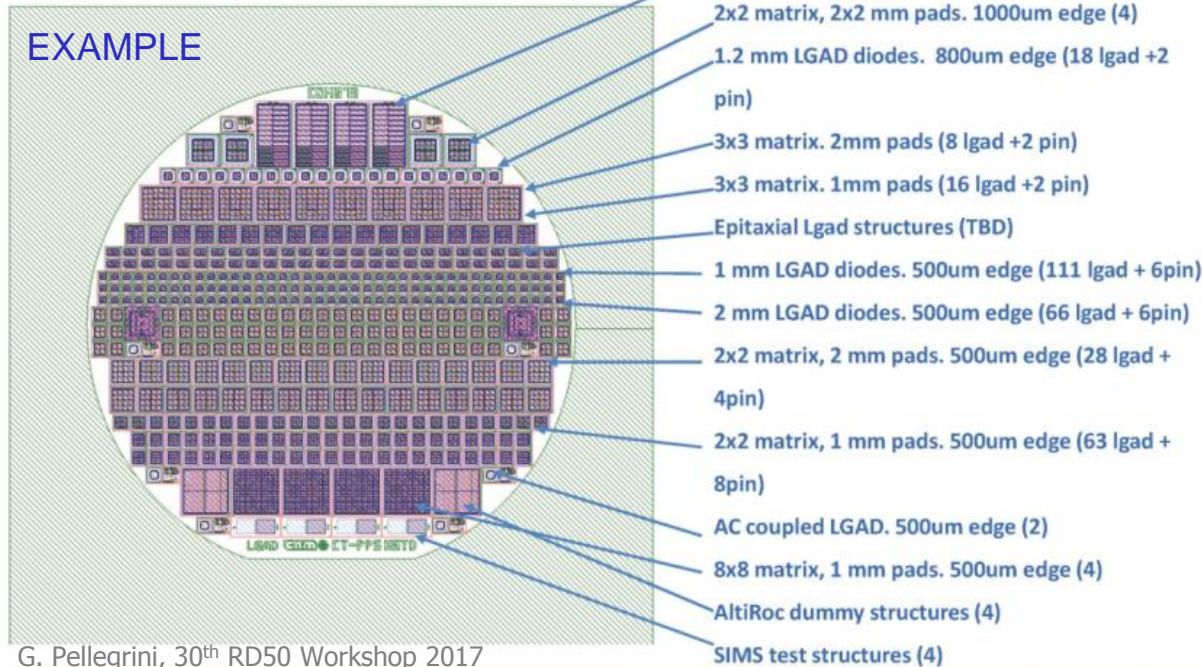
G. Pellegrini, 30th RD50 Workshop 2017

LGAD Devices

- Variety of different test structures
 - Single pads of different size (1-2 mm), arrays of different pad multiplicity (up to 8x8), partly with UBM option for hybridization (bump-bonding to ASIC), fill factor variations, etc...
- Some runs also include strips/pixels
- New runs with large size sensors ($\sim 2 \times 2 \text{ cm}^2$) being produced

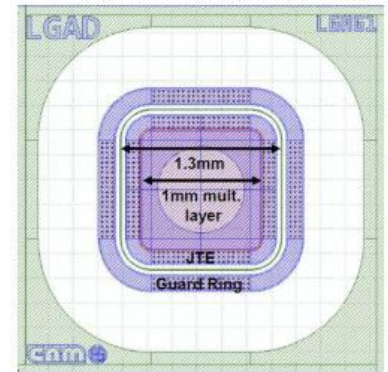
New 4" mask set up

EXAMPLE

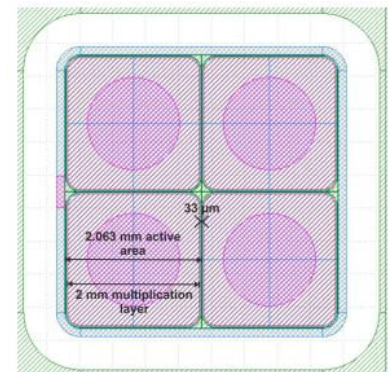


G. Pellegrini, 30th RD50 Workshop 2017

Single Pad

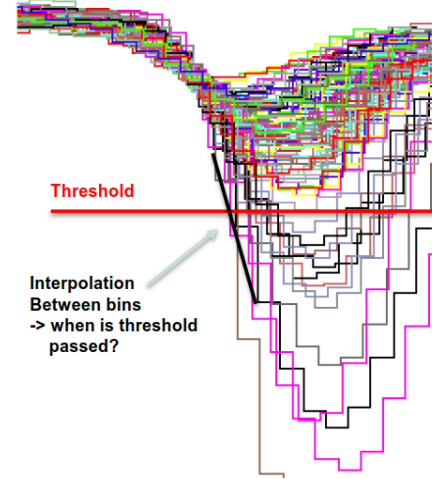


2x2 Array

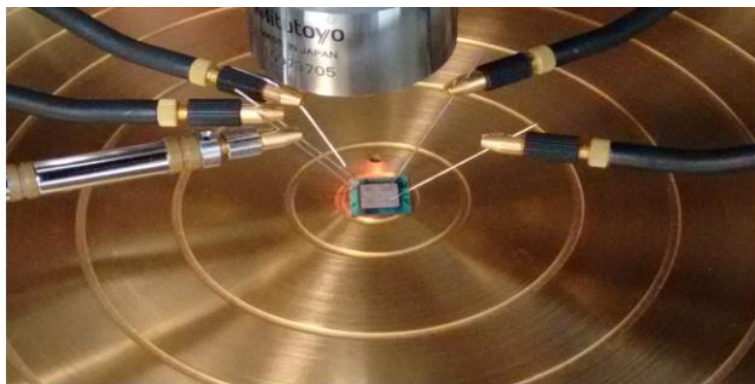


Performance Measurements

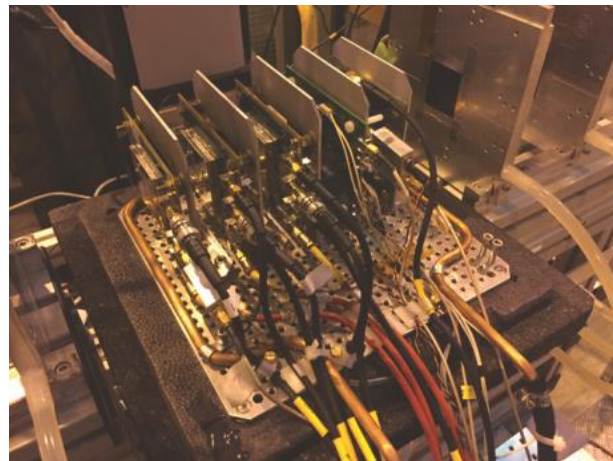
- Laboratory electrical testing (IV, CV)
 - Verify LGAD performance, breakdown voltage, doping level, test yield
- Laboratory dynamic testing (β , α , laser) and beam tests with MIPs
 - Signal shape, noise, charge, gain, time resolution, uniformity
- Time resolution analysis
 - Measured from spread of time difference of ToA of different devices
 - Typically well-known reference device used (good LGAD or Quartz+SiPM ~ 10 ps)
 - Time walk corrected via amplitude/ToT correction or Constant Fraction Discrimination



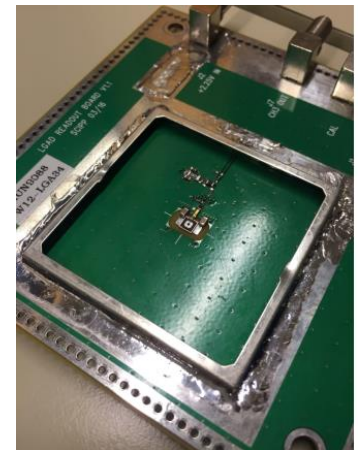
Electrical Testing



HGTD beam test

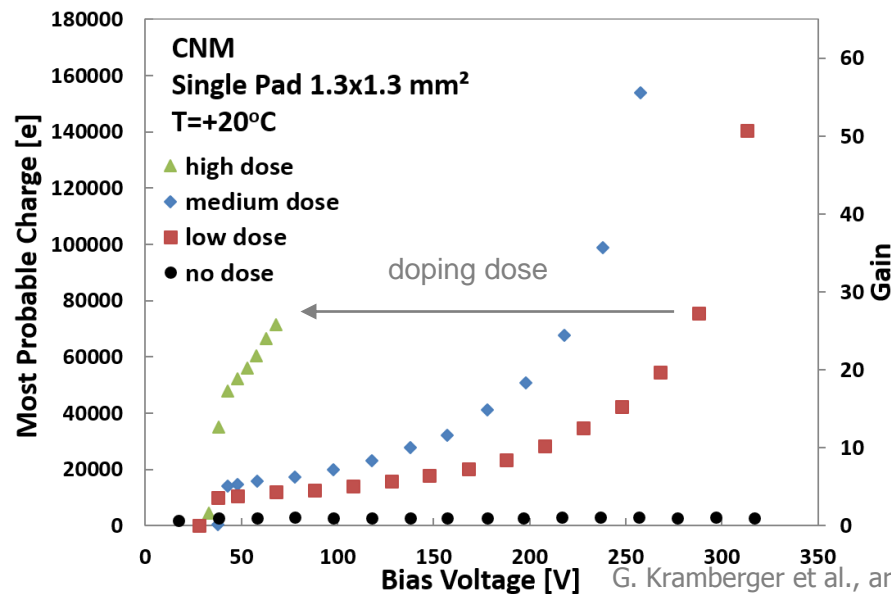
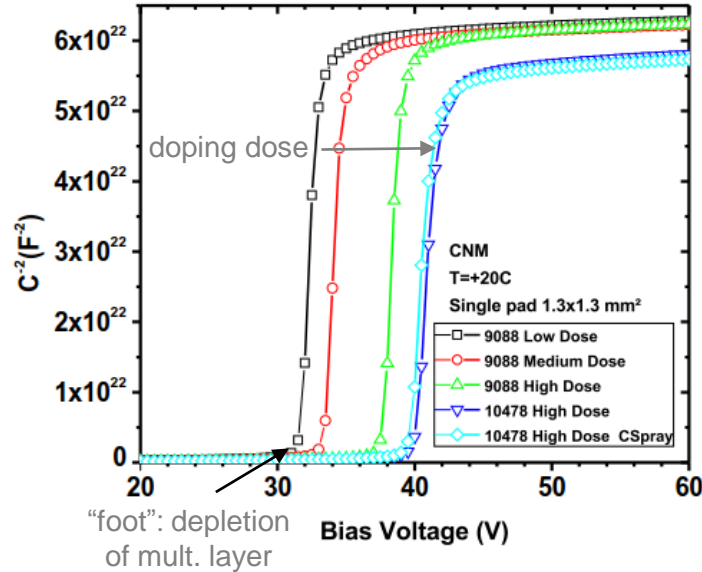
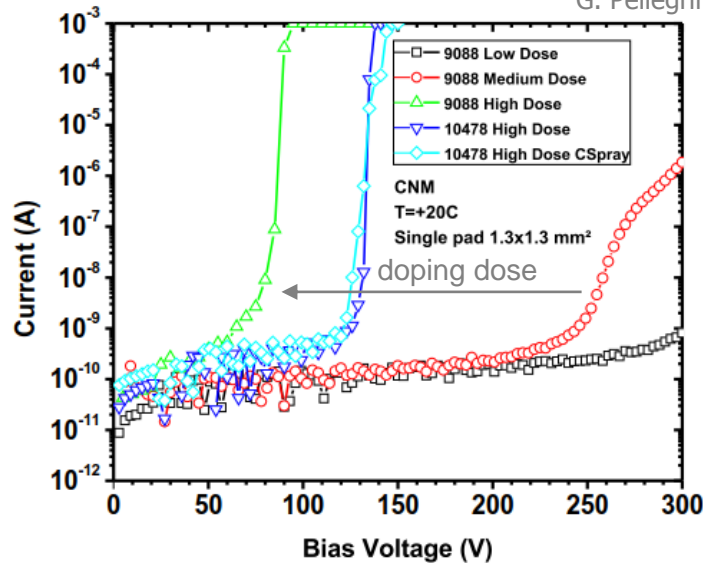


Fast Readout Board



Electrical Characterization and Gain

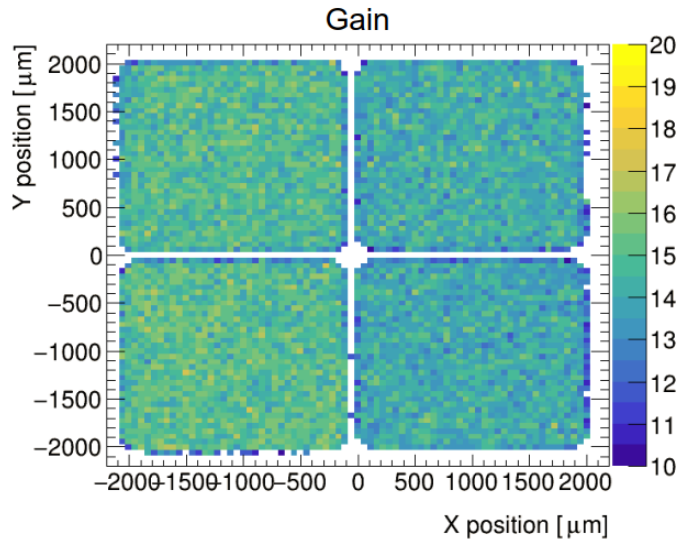
G. Pellegrini, 30th RD50 Workshop 2017



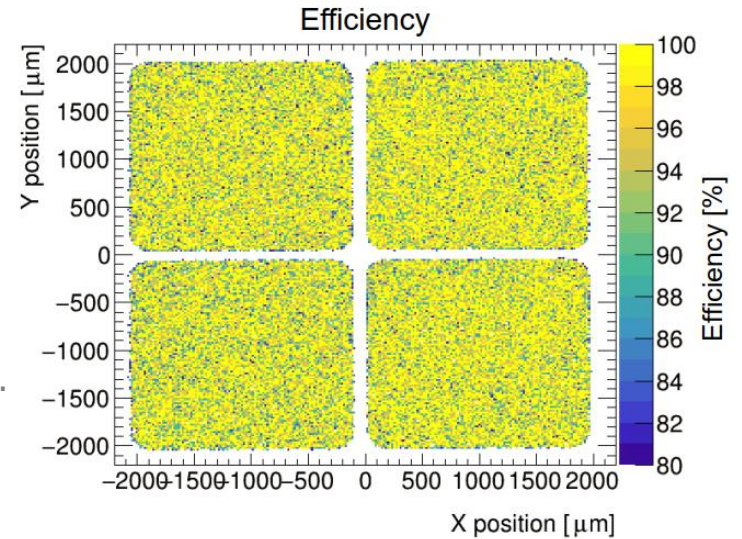
- Break down, depletion of multiplication layer ("foot") and gain depend on dose of multiplication layer
- Gains of up to 50-100 reached (baseline ~20)
 - Need less V for same gain at higher dose

G. Kramberger et al., arXiv:1711.06003

Uniformity in Beam Test

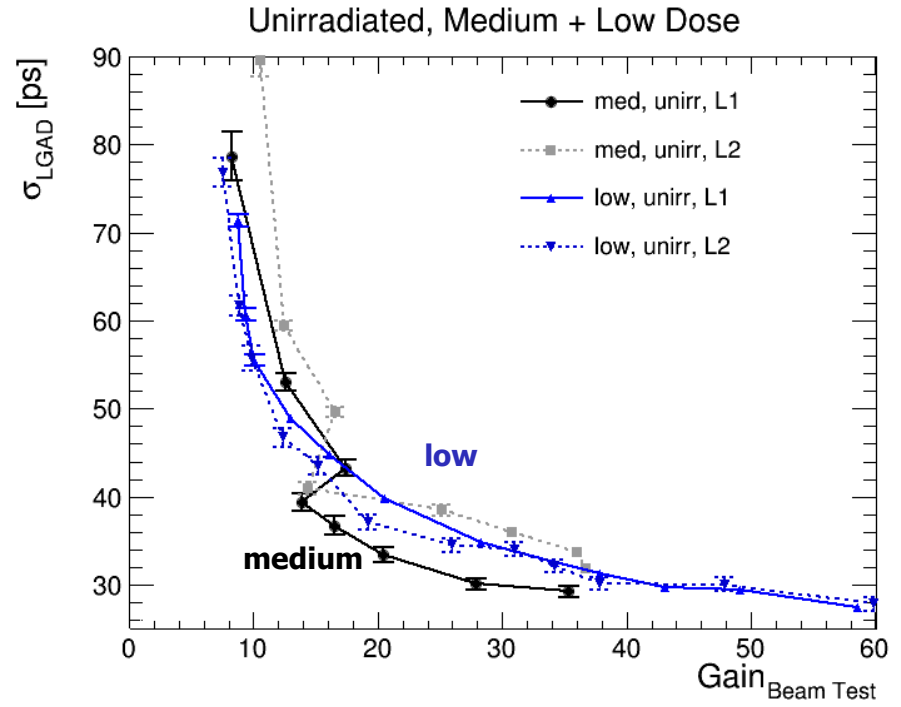
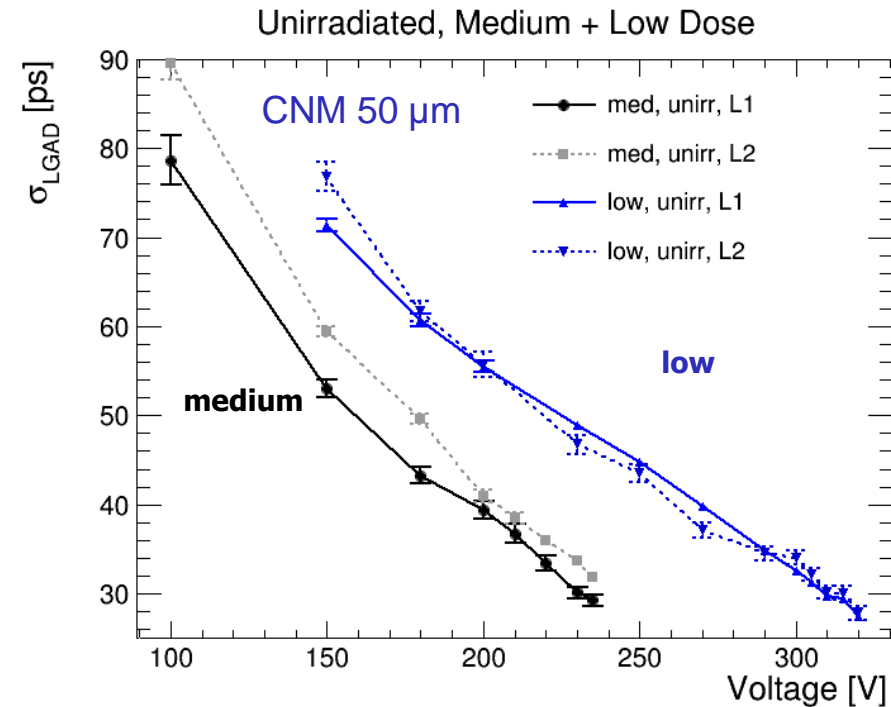


CNM
2x2 Arrays
HGTD Beam Tests
Publication in prep.



- Gain uniform over array
- Hit efficiencies uniformly 96-99%
- 70-100 μm no-gain inter-pad gap for current designs

Time Resolution Unirradiated



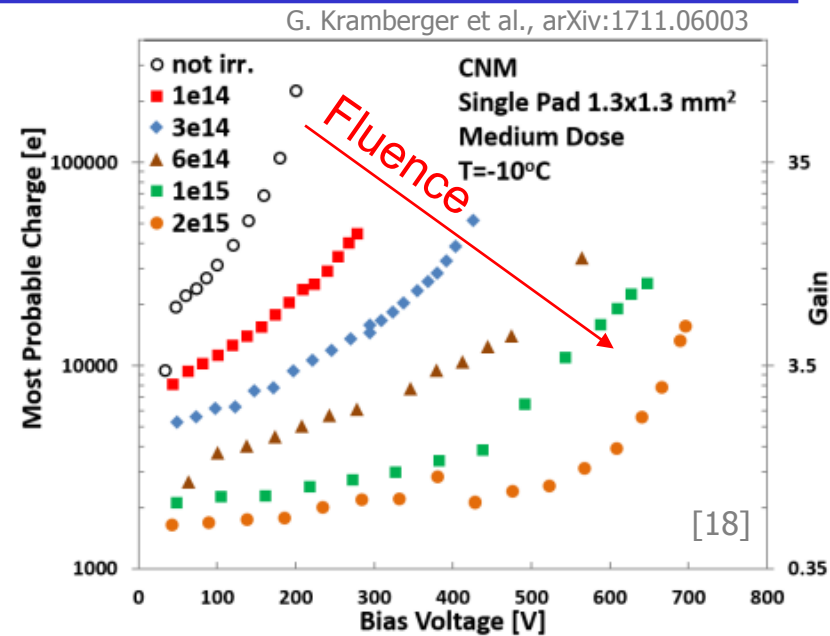
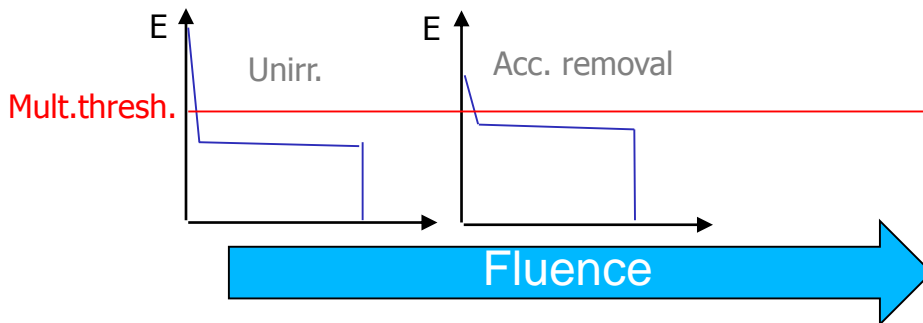
J. Lange et al., JINST 12 (2017) P05003

- Time resolution <30 ps / layer achieved
- Higher V needed for lower dose for same performance
- Universal behaviour as a function of gain
 - If noise is same and v_{drift} saturated
- Similar performance for all vendors and different groups

N. Cartiglia et al., NIM A850 (2017) 83
 J. Lange et al., JINST 12 (2017) P05003
 HGTD beam test (publication in prep.)
 Z. Galloway et al., arXiv:1707.04961

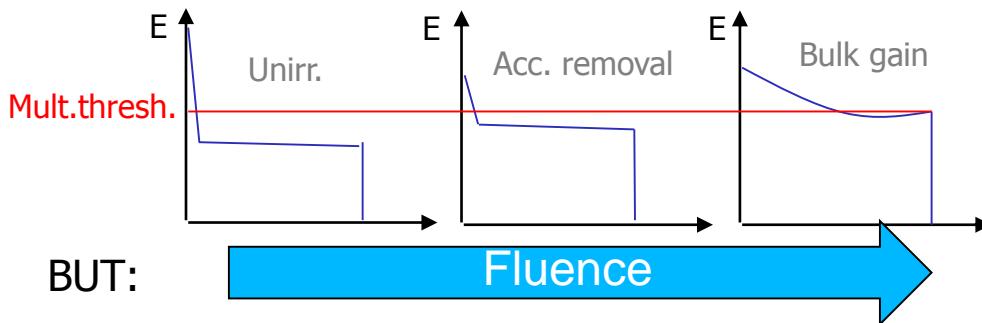
Radiation Effects

- Max. fluence requirements: $\sim 5 \times 10^{15} \text{ n}_{\text{eq}}/\text{cm}^2$
- Trapping of charge carriers
→ mitigated in thin sensors (50 μm)
- Increase of leakage current with fluence
→ mitigated by cooling down to -20 to -30°C
- Modification of effective doping concentration
 - Removal of initial dopants ("acceptor removal")
→ removes multiplication layer
→ degrades gain and time resolution



Radiation Effects

- Max. fluence requirements: $\sim 5 \times 10^{15} \text{ n}_{\text{eq}}/\text{cm}^2$
- Trapping of charge carriers
→ mitigated in thin sensors (50 μm)
- Increase of leakage current with fluence
→ mitigated by cooling down to -20 to -30°C
- Modification of effective doping concentration
 - Removal of initial dopants ("acceptor removal")
→ removes multiplication layer
→ degrades gain and time resolution

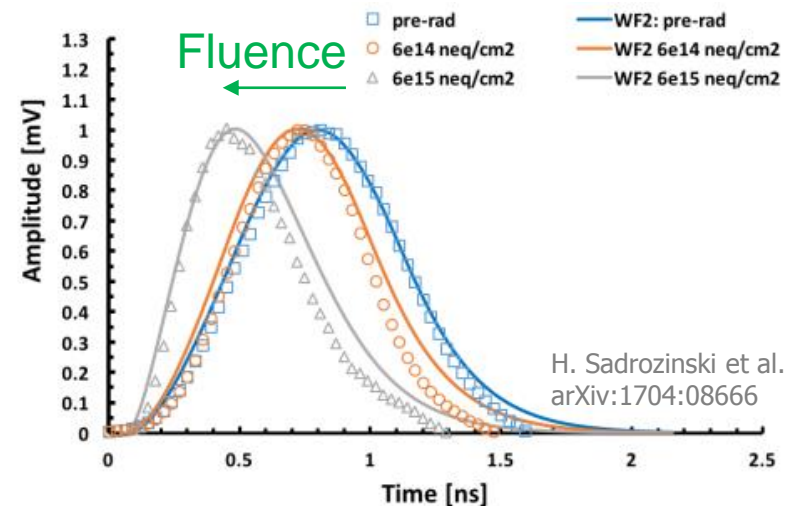
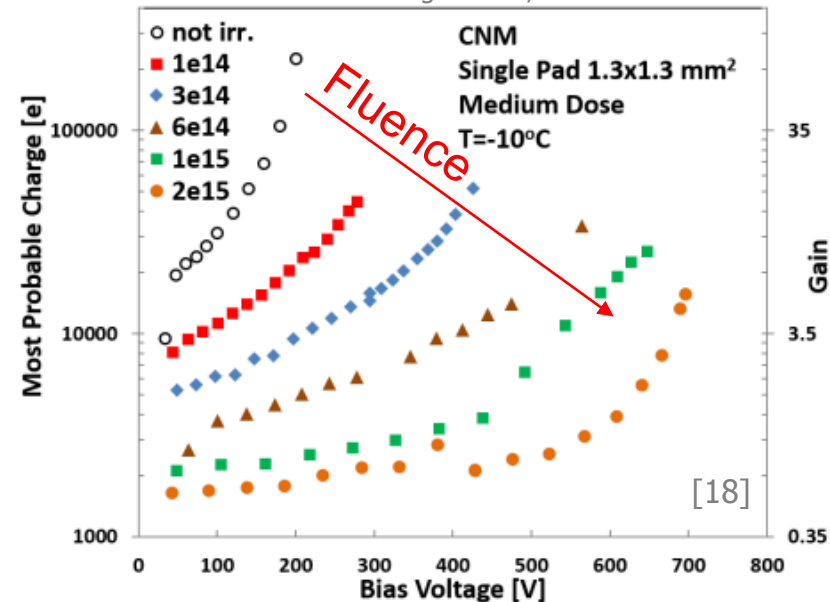


BUT:

- Introduction of radiation-induced acceptor-like defects in bulk
 - Higher break down voltage after irradiation
- introduces gain in the bulk (even in PIN)
→ decrease in rise time
→ partly compensates loss of built-in multiplication layer

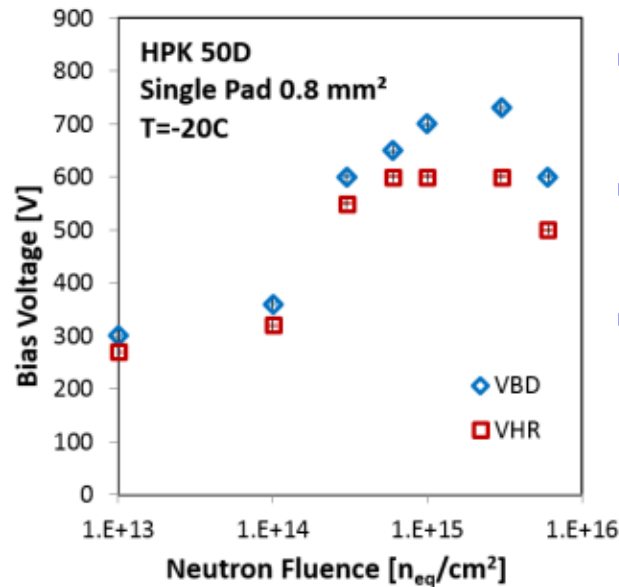
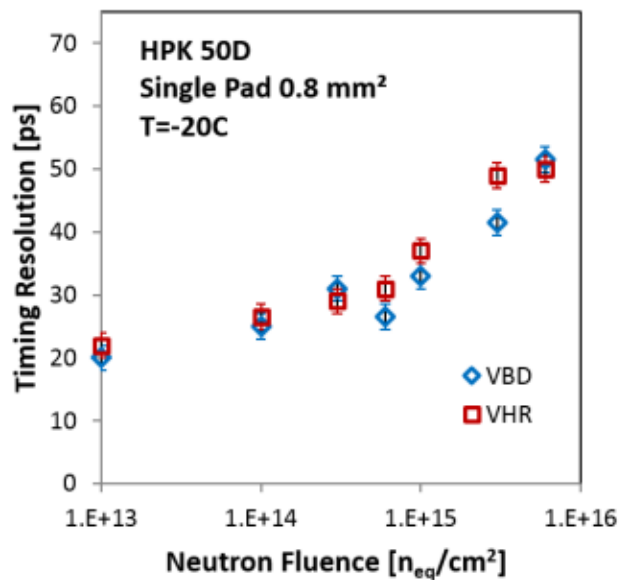
J. Lange et al.,
NIM A622 (2010) 49

G. Kramberger et al., arXiv:1711.06003



H. Sadrozinski et al.,
arXiv:1704:08666

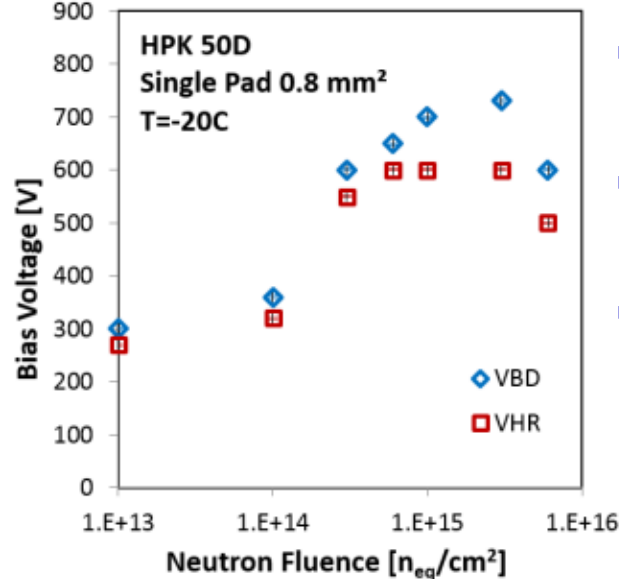
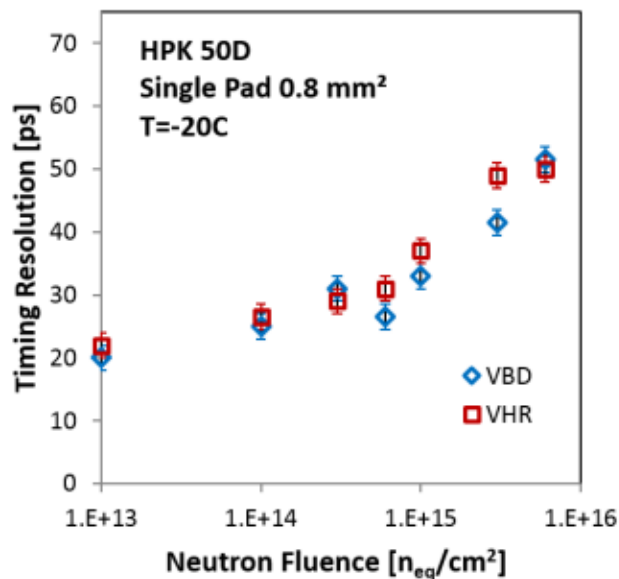
Time Resolution Irradiated HPK 50 μm



- Degradation of time resolution with fluence
- **50 ps/layer maintained up to $6 \times 10^{15} n_{\text{eq}}/\text{cm}^2$**
- 2 operation points studied
 - Bias at break down VBD
 - Bias including “head room” VHR
→ can afford 10% less than VBD

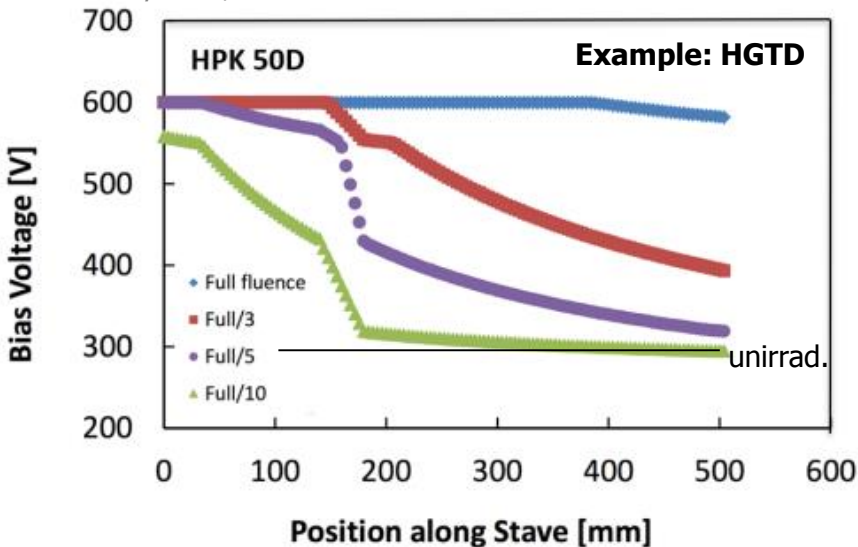
Z. Galloway et al., arXiv:1707.04961

Time Resolution Irradiated HPK 50 μm



- Degradation of time resolution with fluence
- **50 ps/layer maintained up to $6 \times 10^{15} n_{\text{eq}}/\text{cm}^2$**
- 2 operation points studied
 - Bias at break down VBD
 - Bias including "head room" VHR \rightarrow can afford 10% less than VBD

Z. Galloway et al., arXiv:1707.04961

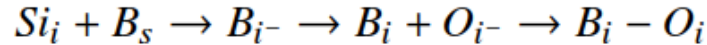


Operational aspects

- Vop needs steady adjustment responding to radiation damage as a function of radius
 - For HPK 50D from 300-600 V (VHR estimator of Vop)
 - Monitored via ToT and time resolution
- Modules along stave need different Vop
 - Limited ganging

Towards Higher Radiation Hardness

- Goal: reduce acceptor removal



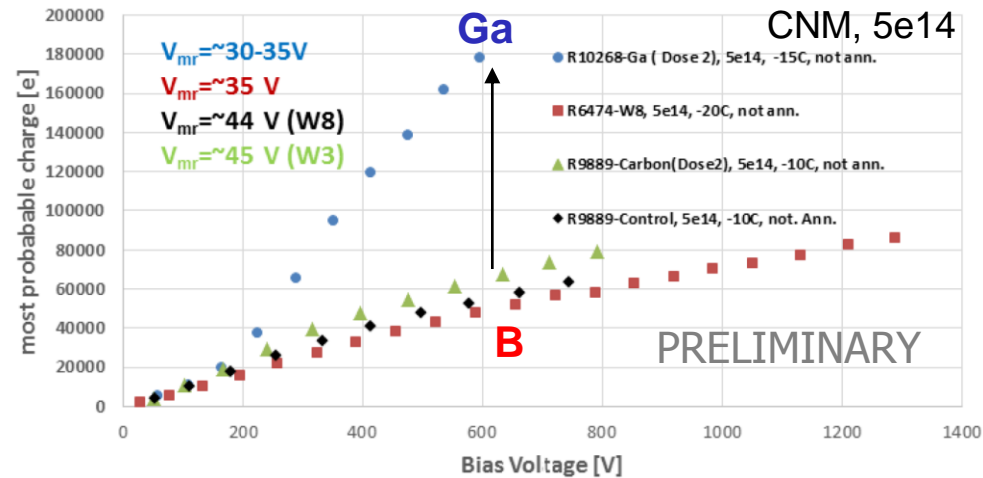
1. Ga heavier than B \rightarrow harder to remove
2. C-spray: C easier to remove \rightarrow sink for Si_i

Ga-LGAD

- First results on CNM 300 μ m Ga-LGAD test structures promising
 - But possible bias due to high initial doping
 - 50 μ m run on-going
 - First results on FBK 50 μ m Ga-LGAD: no effect
- \rightarrow further studies on-going

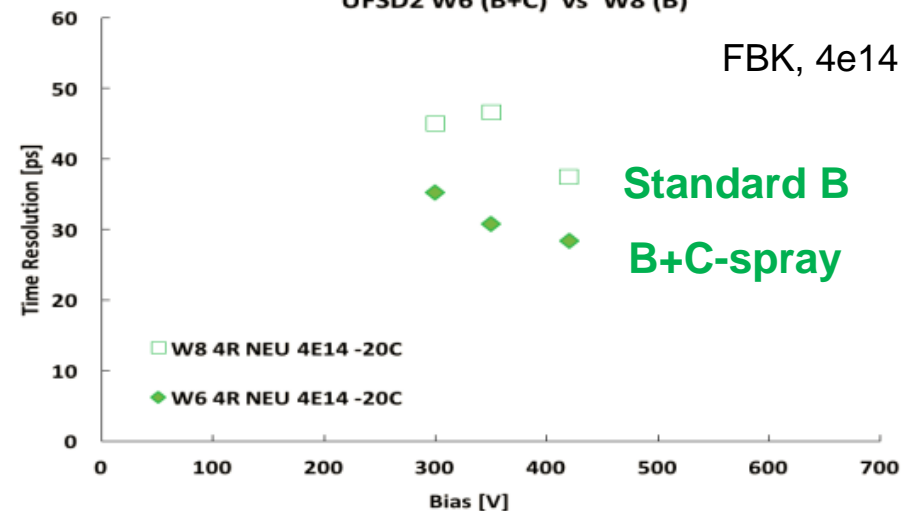
C-spray

- FBK C-spray LGADs have $\frac{1}{2}$ acceptor removal rate than no-C
- Better performance at intermediate fluences $< 1e15 n_{eq}/cm^2$

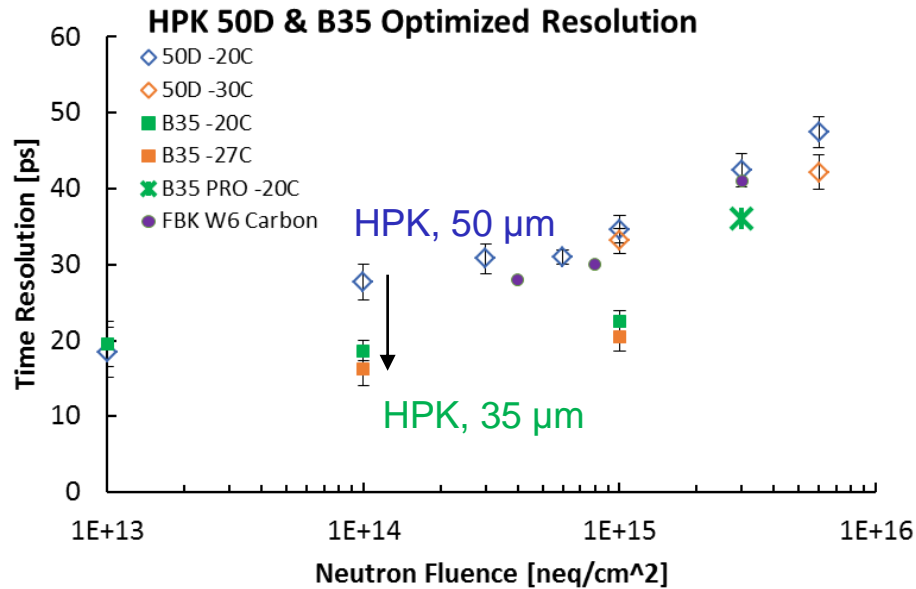


G. Kramberger, 30th RD50 Workshop

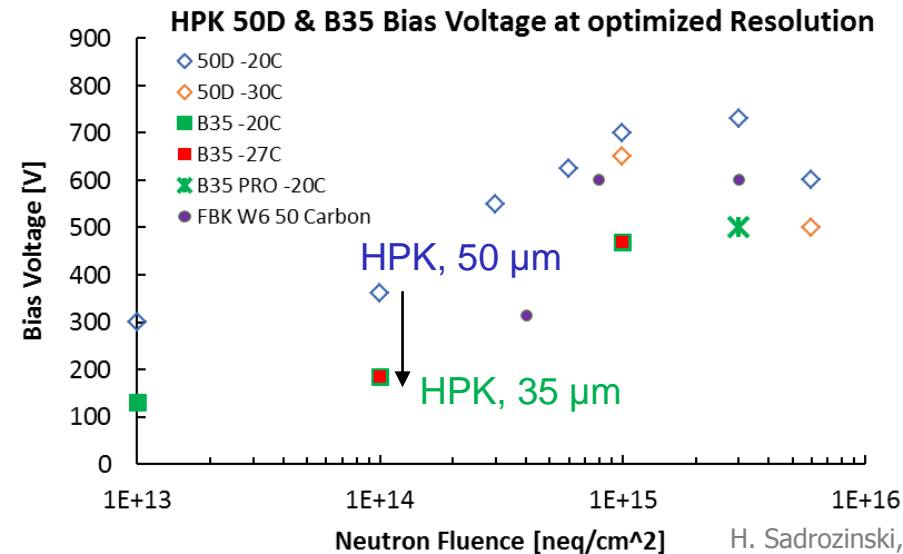
R. Arcidiacono, H. Sadrozinski, TREDI 2018
UFSD2 W6 (B+C) vs W8 (B)



Going thinner... - 35 μm



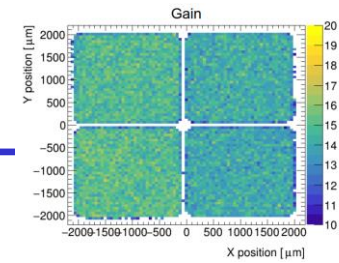
- Significantly better time resolution for 35 μm : ~ 20 ps up to $1\text{e}15$ $n_{\text{eq}}/\text{cm}^2$



- ... at lower bias voltage!

H. Sadrozinski, TREDI 2018

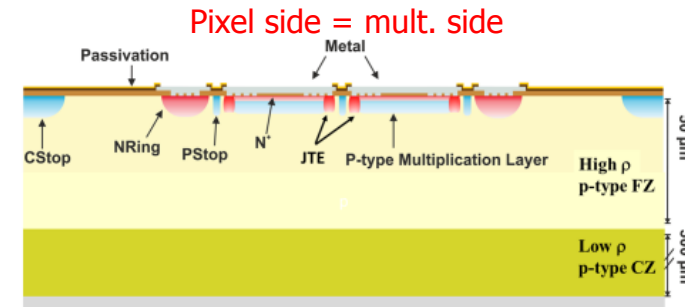
Better Fill Factor – Towards 4D



- First LGAD versions: no-gain inter-pad gap 70-100 μm
 - Only 85% fill factor for 1.3 mm large pads (HGTD) \rightarrow inefficient region
 - Much worse for “real” pixels of $\sim 50 \mu\text{m}$ pitch (e.g. Medipix) \rightarrow needs to be much improved with **final goal of 4D tracking**

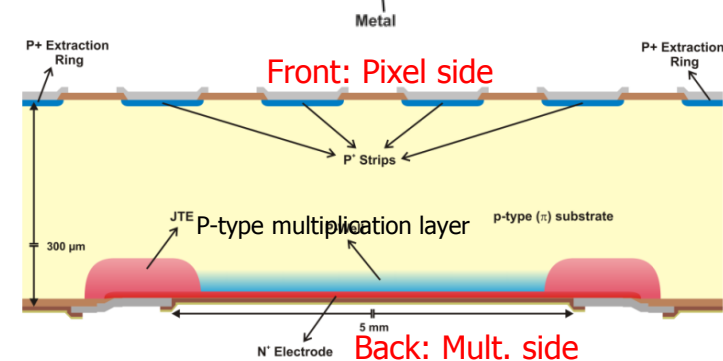
Option 1: Standard LGADs with minimized inter-pad distance

- Optimize or skip JTE around each pixel \rightarrow expect degraded breakdown, but hopefully gain still enough



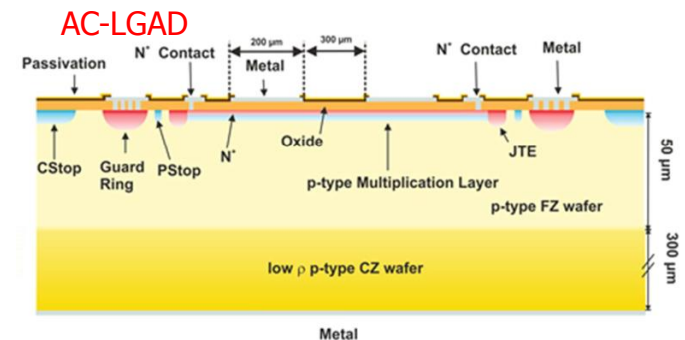
Option 2: inverted LGAD (iLGAD)

- Homogeneous multiplication layer at back-side
- p-in-p pixels at front side: hole collection
- Already working devices produced



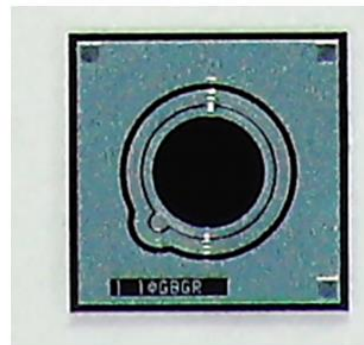
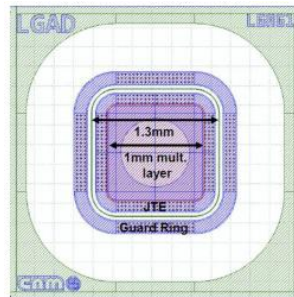
Option 3: AC-LGAD

- Homogeneous multiplication layer at front-side
- Pixelation only in metal, AC-coupled to sensors via SiO_2
- First prototype produced, new dedicated run starts soon



Conclusions

- **Successful development of fast silicon sensors in LGAD technology**
- Several LGAD manufacturers established
- Many RD50, ATLAS, CMS institutes involved in sensor testing in lab and beam tests
- Performance results (50 μm):
 - <30 ps / layer before irradiation
 - 50 ps / layer after $6 \times 10^{15} \text{ n}_{\text{eq}}/\text{cm}^2$
- **→ timing requirements for ATLAS+CMS HL-LHC detectors fulfilled**
- Further intense development on-going for optimisation and to address open questions soon
 - Improved radiation hardness (Ga, C-spray), thinner detectors (35 μm), fill factor, large devices, ...



BACKUP
